

IN THE CLAIMS

1. (original) A method for fabricating a write head, the method comprising:
laying an endpoint on a magnetic flux guide, the endpoint being resistant to milling;
laying a sacrificial edge taper on the flux guide, the sacrificial edge taper having layers of different materials that have different milling rates;
milling the sacrificial edge taper such that the different materials mill at different rates to create a desired angle for a negative mold; and
filling the negative mold with a magnetic material to form a final edge taper for guiding flux to a write pole near the edge taper.
2. (original) The method of claim 1, further comprising:
laying a P3 layer against the final edge taper, the P3 layer comprising a yoke joined to a write pole tip at a flare point, the write pole tip having a tip end that abuts an air bearing surface (ABS) of a disk, wherein a distance from the ABS to the flare point is the same as a combined thickness of the yoke and the final edge taper.
3. (original) The method of claim 1, wherein the milling is ion milling.
4. (original) The method of claim 3, wherein the endpoint resists ion milling.
5. (original) The method of claim 4, wherein the endpoint comprises a material from a group including rhodium, ruthenium, nickel chromium and copper.
6. (original) The method of claim 1, wherein the edge taper is a leading edge taper.
7. (original) The method of claim 1, further comprising:
layering a trailing edge taper (TET) on a trailing endpoint layer, the trailing endpoint adjacent the write pole; and
milling away the TET to create a taper point.

8. (original) The method of claim 7, wherein the trailing endpoint layer comprises layers of different materials that have different milling rates, thus producing a controlled tapered shape.

9. (original) The method of claim 8, wherein the taper point is between 40° and 50°.

10. (original) The method of claim 8, wherein the trailing endpoint layer comprises a material from a group including rhodium, ruthenium, nickel chromium and copper.

11- 22. (canceled)

23. (original) A method of fabricating a write pole, the method comprising:
incorporating trailing edge taper (TET) material and an endpoint layer into a P3 write pole;

ion milling the P3 write pole to define both the P3 write pole and a TET;

encapsulating the P3 write pole;

providing a planar surface on the P3 write pole using a chemical and mechanical polishing (CMP) process;

tapering the P3 write pole and TET with a combination of resist and ion milling; and
terminating the ion milling when the endpoint layer is exposed during milling, whereby a tapered structure of the P3 write pole is achieved.